

	Hits	Search Text	DBs
1	8	((resist or photoresist) near12 pattern) and (resin\$4 same (water\$5soluble) same (thicken\$5 or enhanc\$4 or smooth\$6 or shrinking or coat\$4) same (cationic or ester or (quaternary near5 amide)) same (surfactant)) and (surfactant same (cationic or anionic or amphoteric))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
2	6	((resist or photoresist)) and (resin\$4 same (water\$5soluble) same (thicken\$5 or enhanc\$4 or smooth\$6) same (thickness or micron or Angstrom)) and (surfactant same (cationic or anionic or amphoteric))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
3	0	((resist or photoresist)) and (resin\$4 same (water\$5soluble) same (thicken\$5 or enhanc\$4 or smooth\$6 or coat\$4) same (thickness or amount or micron) same (vary\$4 or adjust\$4) same (heat\$4 or bak\$4)) and (surfactant same (cationic or anionic or amphoteric))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB